## AMENDMENTS TO THE CLAIMS

Please cancel claims 1-9.

## Claims:

1-9 (Cancelled)

10. - 17. (Cancelled)

18. (Amended) A method for producing high purity colloidal silica and a high purity potassium hydroxide, said method comprising the steps of:

providing a quantity of potassium silicate;

subjecting said quantity of potassium silicate to an a cation exchange process to remove a first portion of potassium therefrom to produce a quantity of colloidal silica and a potassium enriched ion exchange resin;

washing said quantity of colloidal silica with water in an ultrafiltration device to produce a quantity of high purity colloidal silica;

regenerating said potassium rich ion exchange resin with an acid to produce a potassium salt solution;

subjecting said potassium salt solution to evaporation and crystallization to remove sodium therefrom to produce a quantity of high purity potassium salt solution;

subjecting said quantity of high purity potassium salt solution to electrodialysis and/or electrolysis to produce a high purity solution of potassium hydroxide; and

adding a portion of said high purity potassium hydroxide solution while washing said quantity of colloidal silica to produce a high purity colloidal silica, suitable for use in the manufacture of CMP slurries.

- 19. (Previously amended) The method of Claim 18, wherein said colloidal silica has a sodium concentration of less than about 10 ppm.
- 20. (Previously amended) The method of Claim 18, wherein said high purity colloidal silica has a sodium concentration of less than about 1 ppm.

## 21. - 22. (Cancelled)

- 23. (Previously Amended) The method of Claim 18, wherein said high purity potassium hydroxide solution has a sodium concentration of less than about 100 ppm.
- 24. (Previously Amended) The method of Claim 18, wherein said high purity potassium hydroxide solution has a sodium concentration of less than about 10 ppm.
- 25. (Cancelled)